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(71) Applicant *(for all designated States except US)*: **ADAPTIVE PLASMA TECHNOLOGY CORPORATION** [KR/KR]; 1 Yeongtong-dong, Yeongtong-gu, Suwon-si, Gyeonggi-do 443-808 (KR).

(72) Inventors; and
(75) Inventors/Applicants *(for US only)*: **SONG, Yeong Su** [KR/KR]; 101- 1205 Sinhan Apt., Sinha 6-ri Bubal-eup Icheon-si, Gyeonggi-do 467-863 (KR). **OH, Sang Ryong** [KR/KR]; 946-1107 Lotte Apt., Yeongtong-dong, Paldal-gu, Suwon-si, Gyeonggi-do 442-470 (KR). **KIM, Sheung Ki** [KR/KR]; 1106-1101 Imaechon Samhwan Apt., Imae-dong, Bundang-gu, Seongnam-si, Gyeonggi-do 463-902 (KR). **KIM, Nam Heon** [KR/KR]; 804-302 Byeokjeokgol Dusan Apt., 973-3 Yeongtong-dong, Paldal-gu, Suwon-si, Gyeonggi-do 442-470 (KR).

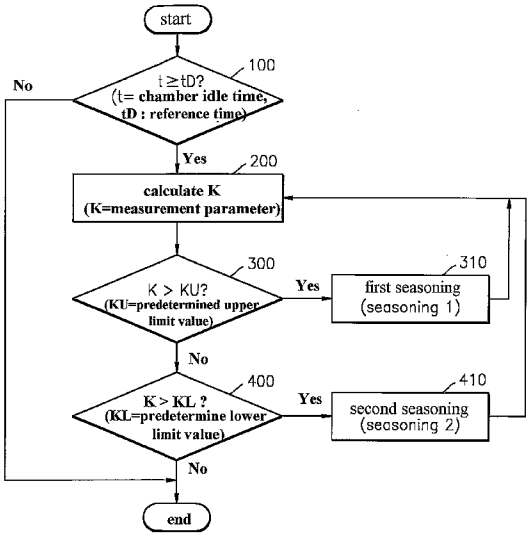
(74) Agent: **AJU PATENT & LAW FIRM**; 12th Floor, Poonglim Building, 823-1 Yeoksam-dong, Kangnam-gu, Seoul 135-784 (KR).

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(54) Title: METHOD AND APPARATUS FOR SEASONING SEMICONDUCTOR APPARATUS OF SENSING PLASMA EQUIPMENT



(57) Abstract: A plasma equipment seasoning method and plasma equipment to which the seasoning method is applied. The seasoning method comprising the steps of measuring the ratio of optical emission intensity of silicon oxide (SiOx)-based chemical species to optical emission intensity of carbon fluoride compound (CFY)-based chemical species present in a process chamber of plasma equipment before operating the plasma equipment to perform a plasma process, determining whether the value of the measured optical emission intensity ratio is within a predetermined range of normal state or not, and, when reaction gas to be used in the plasma process is supplied into the process chamber based on the result of determination such that the value of the measured optical emission intensity ratio is within the predetermined range of normal state, seasoning the interior of the process chamber to change the ratio of components of the reaction gas, and thus, to change the optical emission intensity ratio.

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